

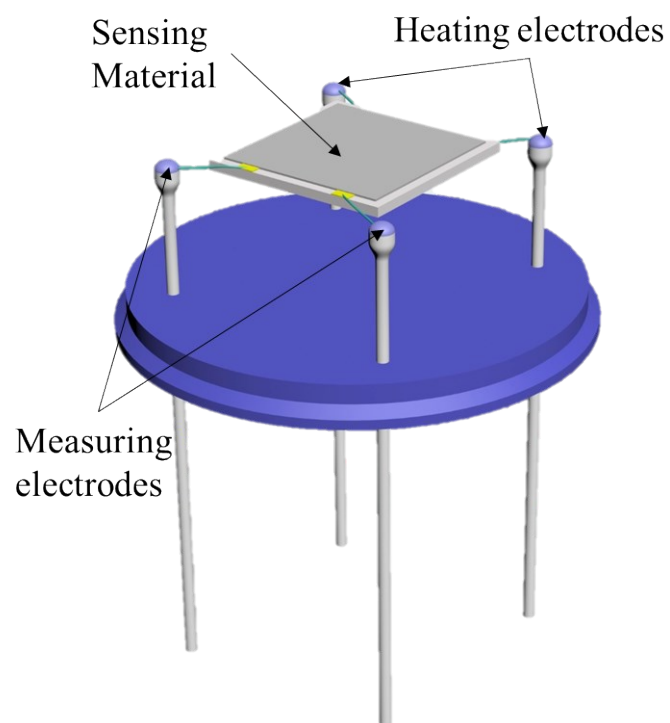
## Supporting Information

SnO-Sn<sub>3</sub>O<sub>4</sub> heterostructural gas sensor with high response and selectivity to parts-per-billion-level NO<sub>2</sub> at low operating temperature

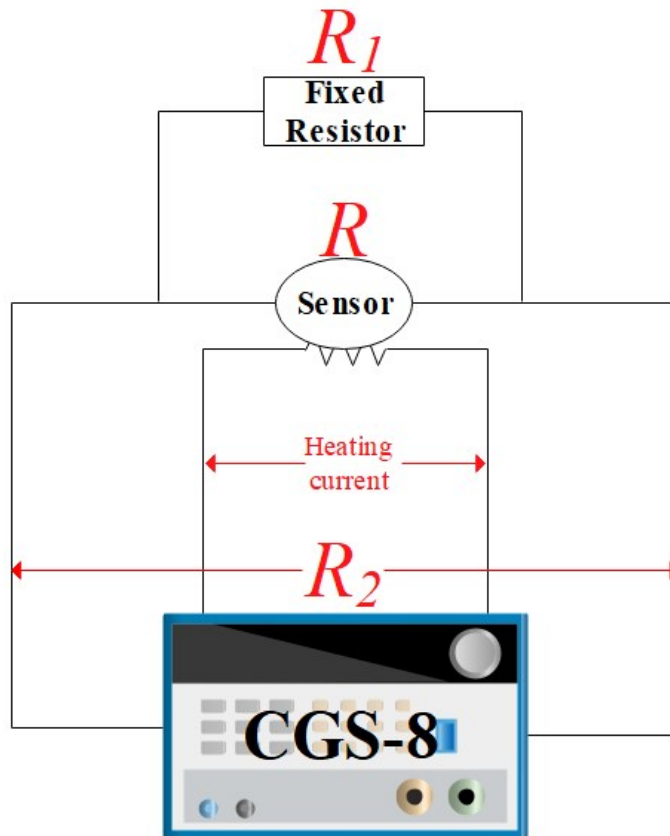
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**Figure S1.** Schematic diagram of the gas sensors used in this study.



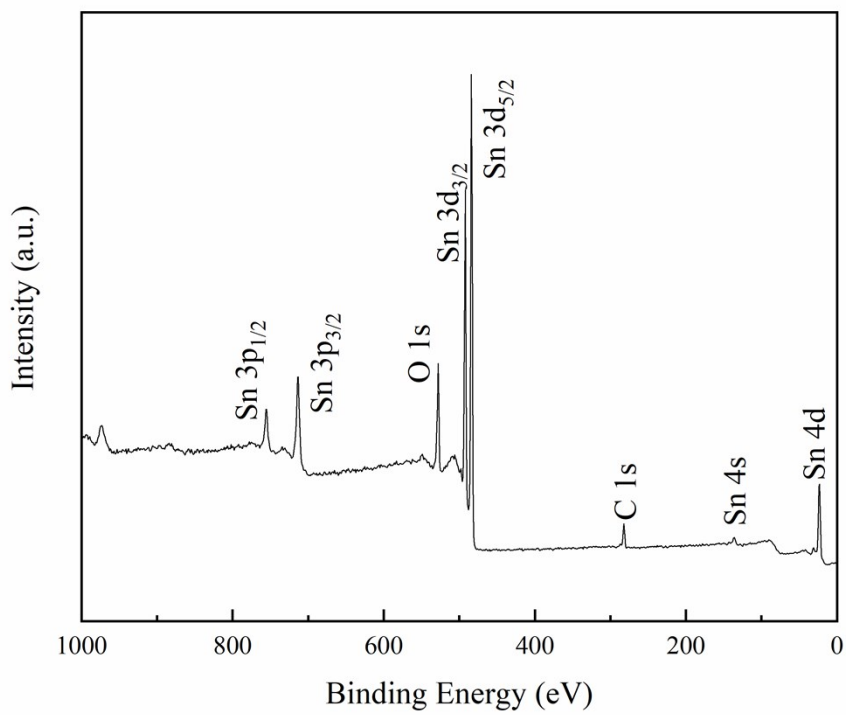
**Figure S2.** Schematic diagram of the measuring circuit used in the tests.

Because of the high resistance of the sensors made by SnO-Sn<sub>3</sub>O<sub>4</sub> heterostructure, their resistances might exceed the measuring range of the test system (500 MΩ) when exposed to high concentrations of NO<sub>2</sub>. Hence the circuit above was used to enlarge the measuring range. In Figure S2,  $R_1$  was the resistance value of a fixed resistor (a resistor with 470MΩ nominal value was used here), which was parallel connected with the gas sensor.  $R$  was the resistance of the gas sensor, which was the value we ultimately need.  $R_2$  was the resistance value measured by CGS-8 intelligent gas sensing analysis system. For these three factors,

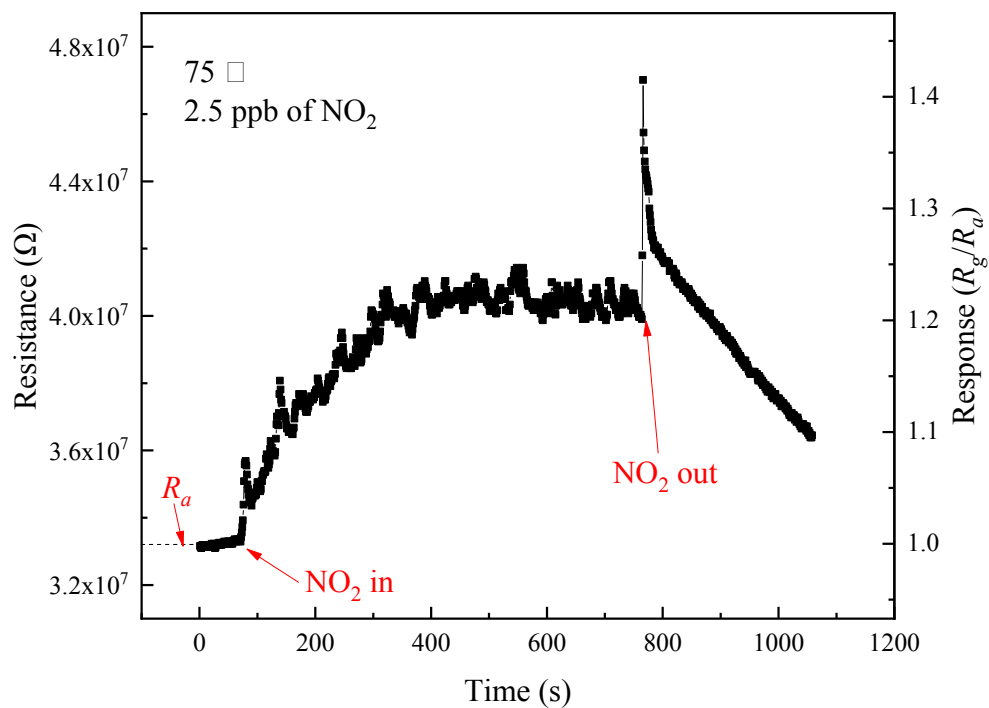
$$\frac{1}{R_1} + \frac{1}{R} = \frac{1}{R_2}$$

So,

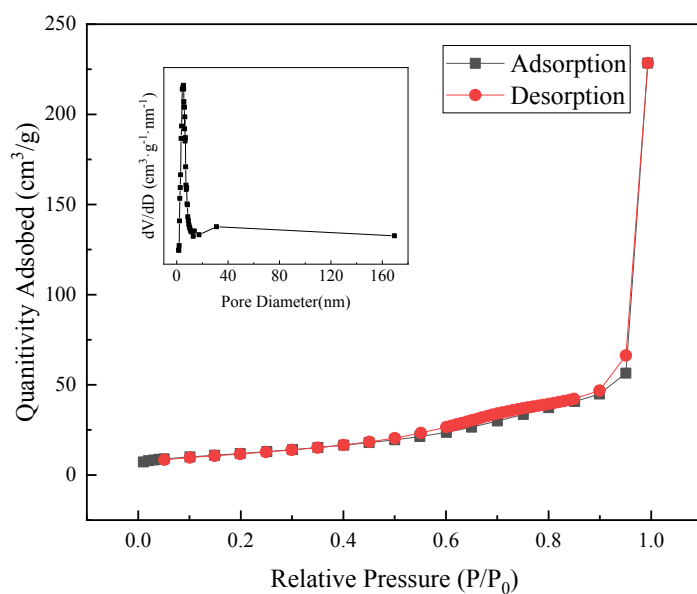
$$R = \frac{R_1 * R_2}{R_1 - R_2}$$



**Figure S3.** General scan X-ray photo electron spectra of as-prepared sample.



**Figure S4.** Resistance and response curve of SnO-Sn<sub>3</sub>O<sub>4</sub> heterostructure when exposed to 2.5 ppb NO<sub>2</sub> at 75 °C.



**Figure S5.** N<sub>2</sub> adsorption–desorption isotherm of the SnO–Sn<sub>3</sub>O<sub>4</sub> heterostructure and corresponding pore size distribution.